



Featuring work from Mario Ochoa and Pablo Roldán-Varona *et al.* at the Photonics Engineering Group, Universidad de Cantabria, Santander, Spain.

Polarisation-independent ultrafast laser selective etching processing in fused silica

Ultrafast laser selective etching achieved without light polarisation control, using few femtosecond pulses of low energy and NaOH etching solutions; targeting high aspect ratios and enhanced surface qualities. This ultrafast laser selective etching process enables simple fabrication of complex 3D microfluidic channels and non-planar arbitrary shapes in fused silica.

As featured in:



See Mario Ochoa and Pablo Roldán-Varona *et al.*, *Lab Chip*, 2023, **23**, 1752.